

*“Probing the intrinsic limitations of the contact resistance of metal/semiconductor interfaces through atomistic simulations”*. Pourtois G, Dabral A, Sankaran K, Magnus W, Yu H, de de Meux AJ, Lu AKA, Clima S, Stokbro K, Schaekers M, Houssa M, Collaert N, Horiguchi N, Semiconductors, Dielectrics, And Metals For Nanoelectronics 15: In Memory Of Samares Kar , 303 (2017). <http://doi.org/10.1149/08001.0303ECST>